

Project Name	Republic of Singapore / Photomask Line Production Automation Demonstration Project		
Company Name	Tekscend Photomask Corp.	Company Size	SME • Other than SME
Category	Category 1 • Category 2 • Category 3	Project Field	GX • DX • Economic Security
Total Project Expenses/Total Subsidy Expenses/ Subsidy Application Amount	9.27 billion yen /8 billion yen /4 billion yen		

Project Outline

【Project Scheme】

Tekscend Photomask Corp.
(Grant applicant)

100% owned

Tekscend Photomask
Singapore Pte. Ltd.
(Local subsidiary)

【Outline】

- Establish an automated production line for cutting-edge 28nm photomasks in Singapore to achieve increased production capacity and cost reduction.

【Key Technologies and Demonstrations】

- Technology transfer of Tekscend Photomask's cutting-edge 28nm photomask process for ArF lithography, and demonstration of the first automated line construction by an external mask manufacturer
- By introducing EAP (Equipment Automation Process), FDC (Fault Detection Clarification), EDA (Engineering Data Analysis), etc., we achieved a photomask production line with 1.5 times the productivity per worker and a 15% improvement in yield.

【Schedule】

- April 2026~ Equipment installation
- B of 2027 Sequential production start
- March 2029 Automation verification evaluation completed
- April 2031 New automated lines established in Japan

【Rendering of the New Singapore Factory】



Resulting benefits to Japan

【Points that this project contributes to innovation creation in Japan】

- Acquired the industry's first high-productivity automated line technology for external photomask sales, attracting 50 highly skilled local personnel

【Resulting domestic employment and investment benefits】

- Establish production lines utilizing proven automation technologies at two locations in Japan
- Expand the local semiconductor industry by constructing an advanced mask line in Singapore
- Promote sales of Japanese-made semiconductor equipment in Singapore